To: Distribution

From: R. Walker

Subject: Minutes of ITS Planning Meeting

Date: 2 January 1997

Attendees: C. Bohn, G. Neil, C. Sinclair, G. Biallas, R. Legg, and R. Walker

The purpose of today's meeting was to plan for the best utilization of effort for the ITS.

G. Biallas presented new resistance data on the coated ceramics (5 x 10^11 Ω extrapolated) and the ion implanted sample wafers (1.1 to 1.8 x 10^11 Ω on best wafer). The desired resistance is thought to be about 5 x 10^10 Ω. It was felt that both approaches could be improved by continued application of coating and ion implantation respectively.

The various options for the gun ceramics and stalk and their expected ready for installation dates are given below.

Option	**Task Time**	**Ready Date**
1. Use existing gun ceramics.		Now
a) Measure existing ceramics resistance	0.5 wk.	
b) Bake gun and beam line	2.0 wk.	
c) Debug and calibrate equipment	1.0 wk.	
d) Learn how to operate new system	0.5 wk.	
e) Make and life test cathodes	1.0 wk.	
f) Repeat parts of transverse experiment	1.0 wk.	
g) Run portion of 350 Kev experiment at lower voltage	1.0 wk.	
2. Install coated gun ceramics		4 February
a) Braze ceramics with rings	2.0 wk.	
b) Weld and leak checks	1.5 wk.	
3. Install ion implanted ceramics		4 February
a) Ion implant ceramics	0.5 wk.	
b) Braze ceramics with rings	2.0 wk.	
c) Weld and leak checks	1.5 wk.	
4. Install stalk coated by FM with existing ceramics		7 February
a) Coat and weld stalk	5.0 wk.	

It was decided to: a) proceed with Option 1 and b) monitor Options 2, 3, and 4 as they make progress toward their completion. To complete the 350 Kev experiment, either Option 2, 3, or 4 will be required.